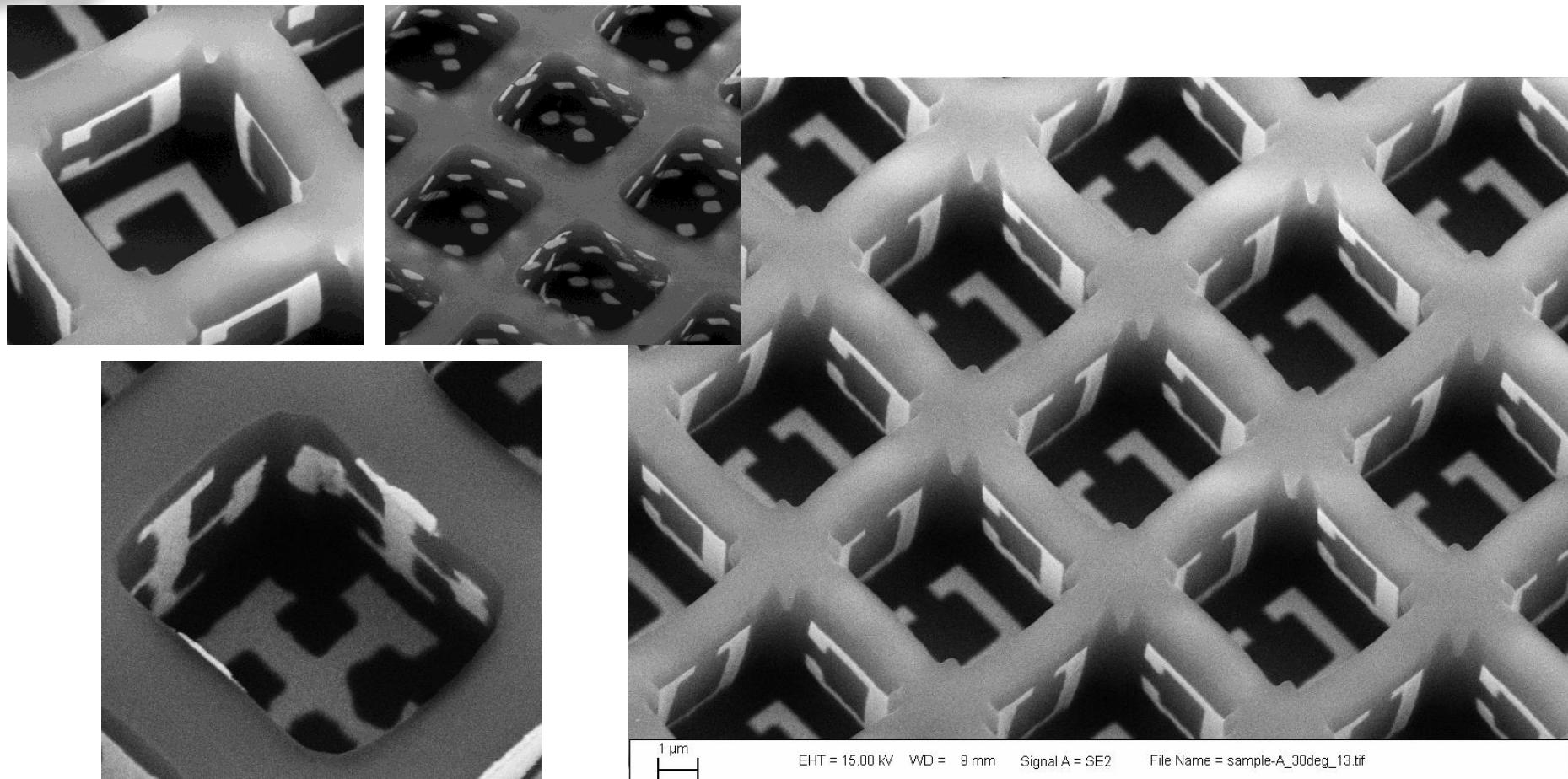


Membrane Projection Lithography

SAND2013-7376P

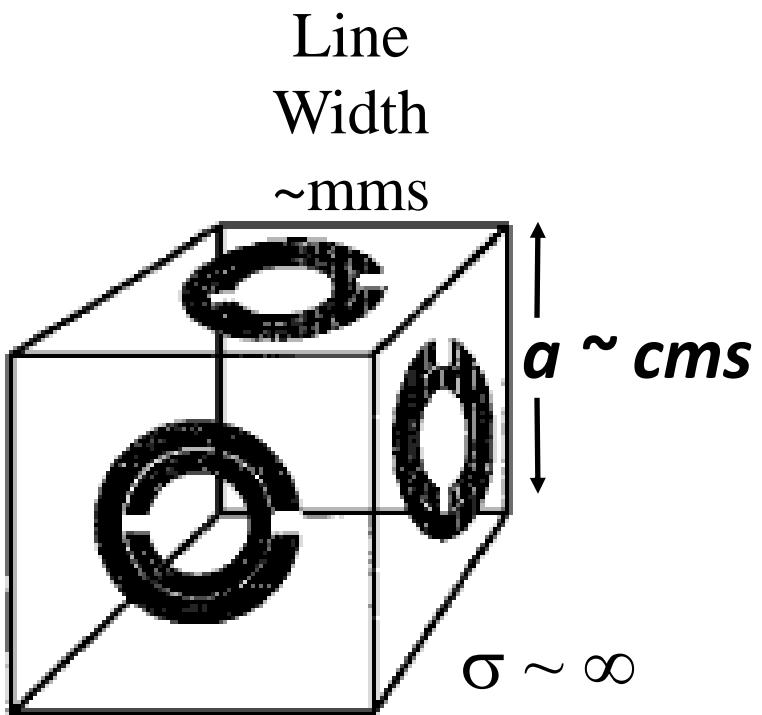


D. Bruce Burkel, Sandia National Laboratories

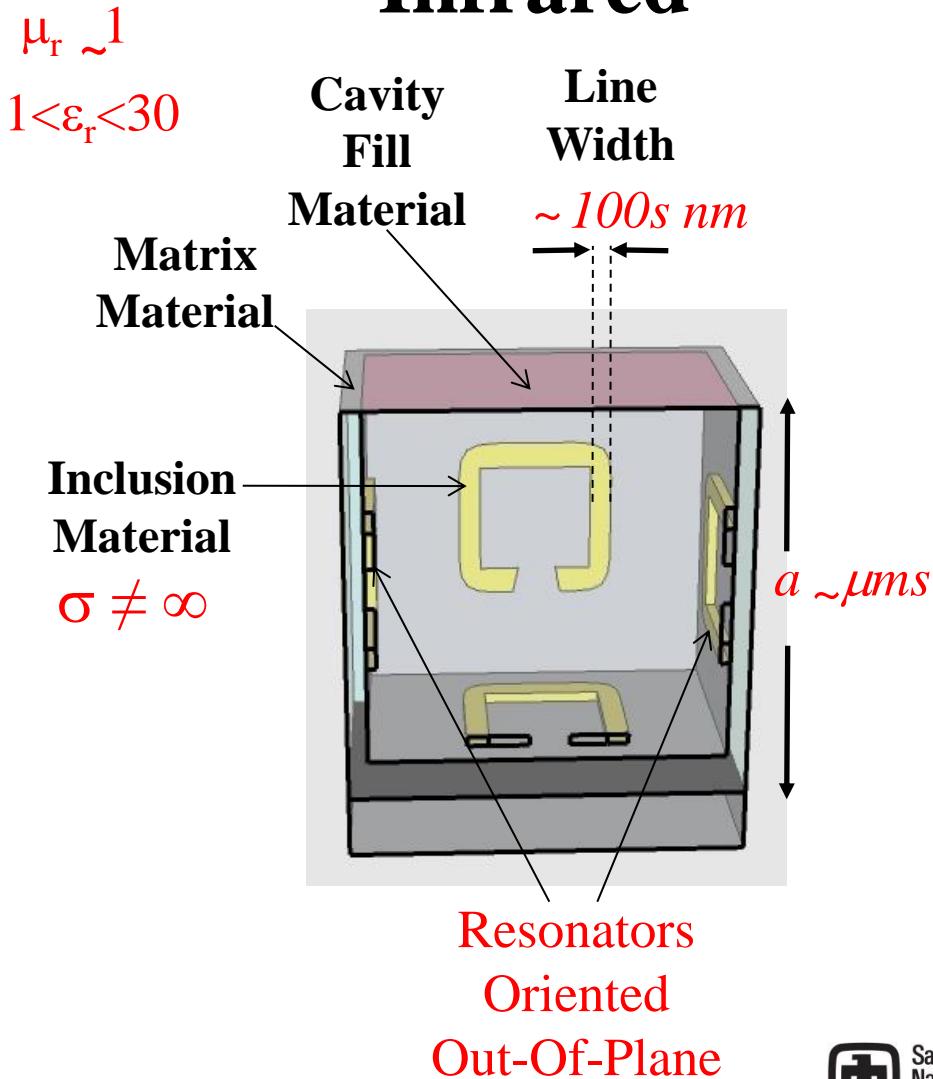
Sandia National Laboratories is a multi-program laboratory managed and operated by Sandia Corporation, a wholly owned subsidiary of Lockheed Martin Corporation, for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-AC04-94AL85000.

Translating a Pendry Cube from Microwave To Optical Frequencies

RF/Microwave

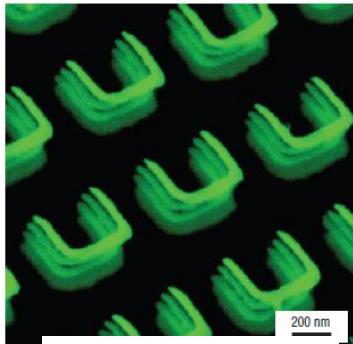


Infrared

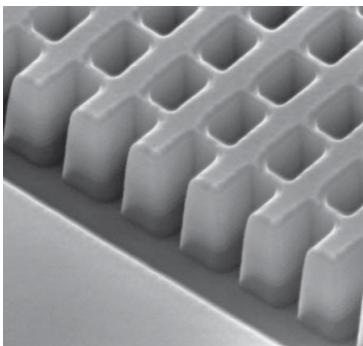


Examples of micro/nanoscale 3D Fabrication Approaches

Layer-by-layer

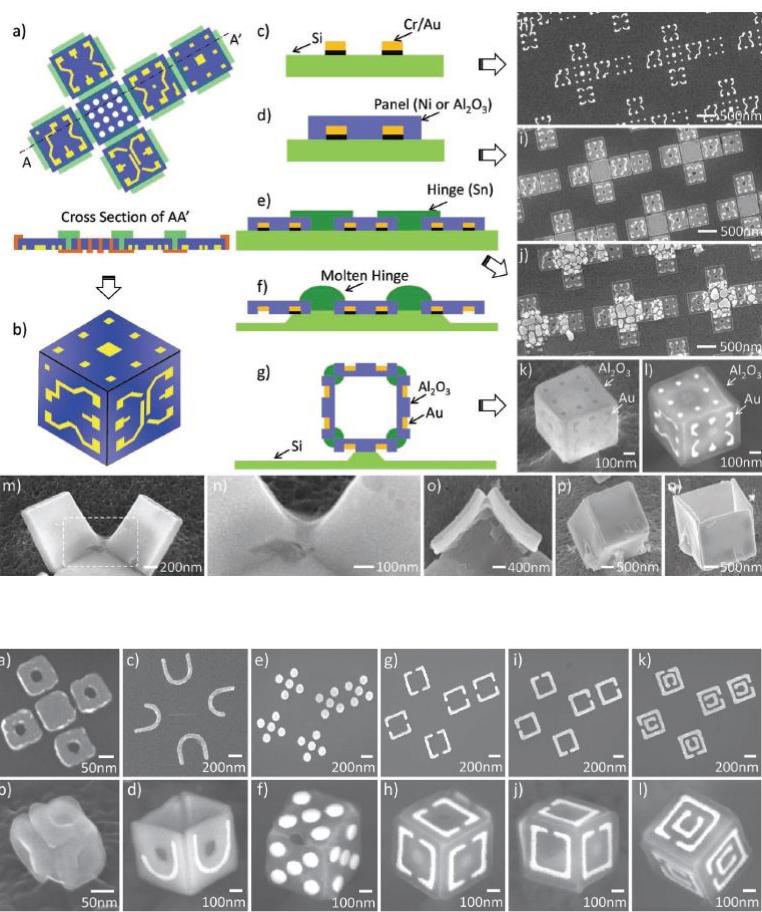


N. Liu, et. al.
Nat. Mat., 7,
pp 31-37, (2008)



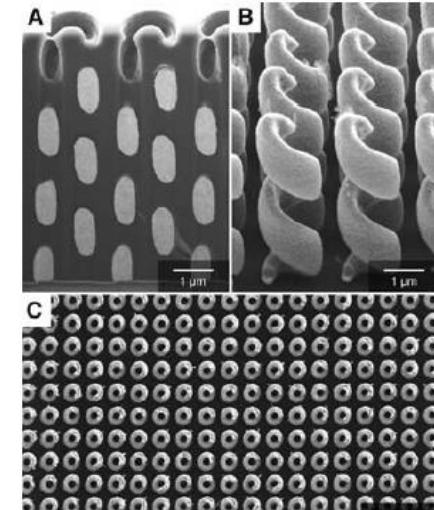
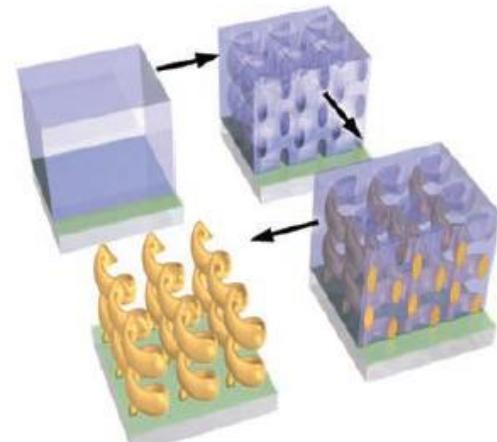
J. Valentine, et. al.
Nature, 455,
pp 376-U32, (2008)

Nano Origami



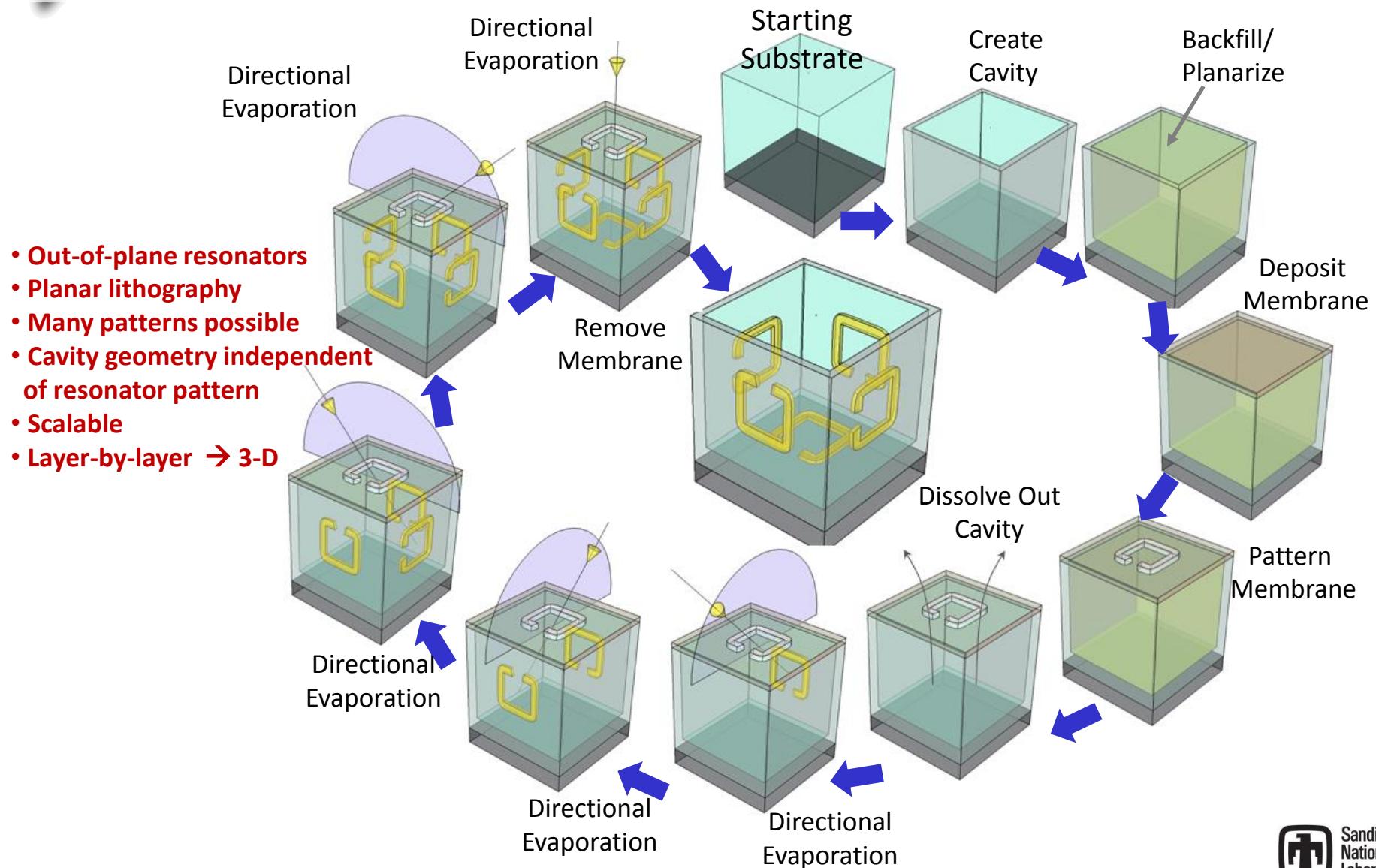
J.H. Cho, et. al. Small, 7,
pp 1943-1948, (2011)

Direct Laser Write



J.K. Gansel, et. al. Science, 325,
pp 1513-1515, (2009)

Membrane Projection Lithography: MPL

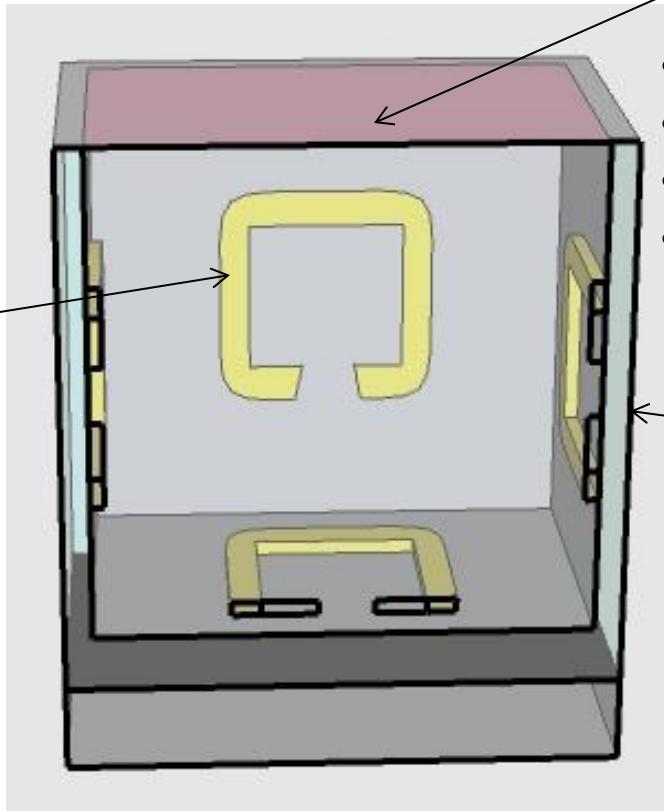


Sandia
National
Labs

Material Components Available in MPL Fabrication

Inclusion Material

- Metals (Au, Al, Ti,...)
- Dielectrics (Ge, Si, Te,...)
- Photoconductors
- Any evaporatable material



Cavity Backfill Material

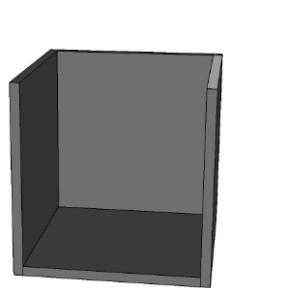
- SU-8
- Polyimide
- Spin-on Dielectrics
- CVD dielectrics (with CMP)

Matrix Material

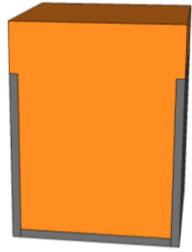
- SU-8
- Polynorbornene
- Si
- Polaritonics

Material set for matrix, membrane and backfill must form a process-orthogonal set

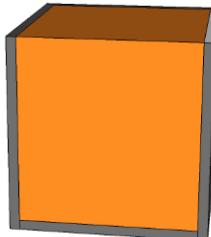
Organic MPL Process Flow



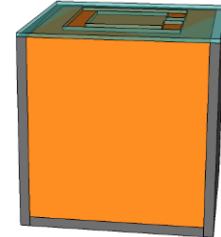
Create Cavity



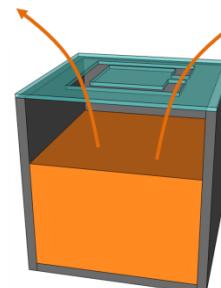
Sacrificial Backfill



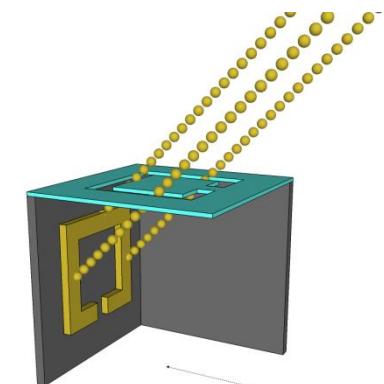
Planarize Backfill



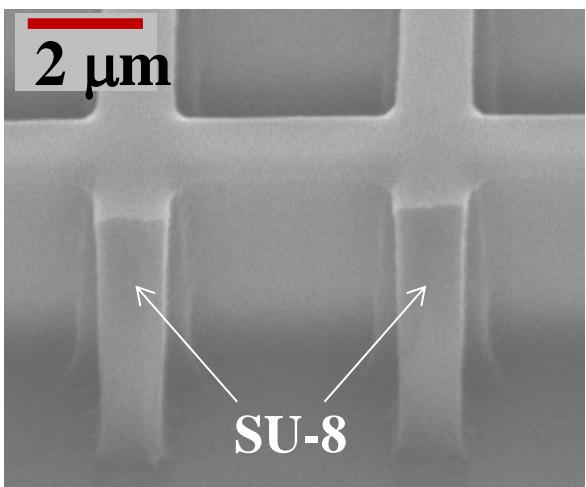
Deposit/Pattern Membrane



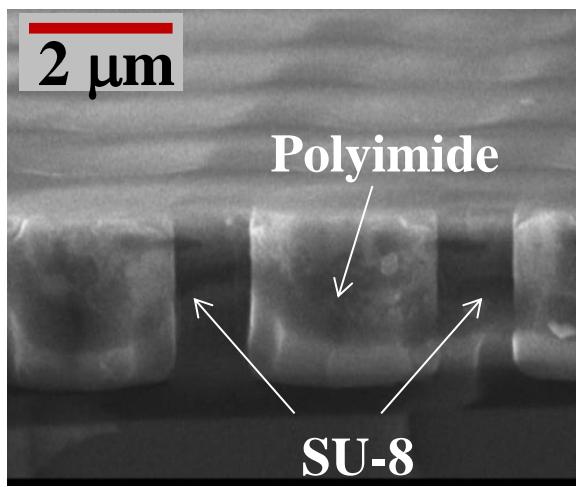
Dissolve Out Backfill



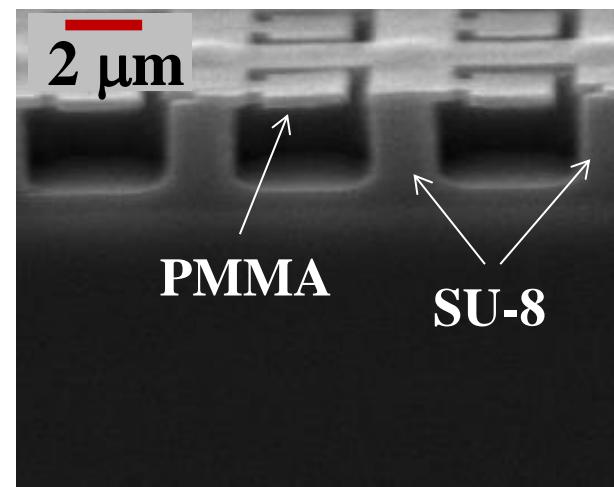
Directional Processing



Create Cavity

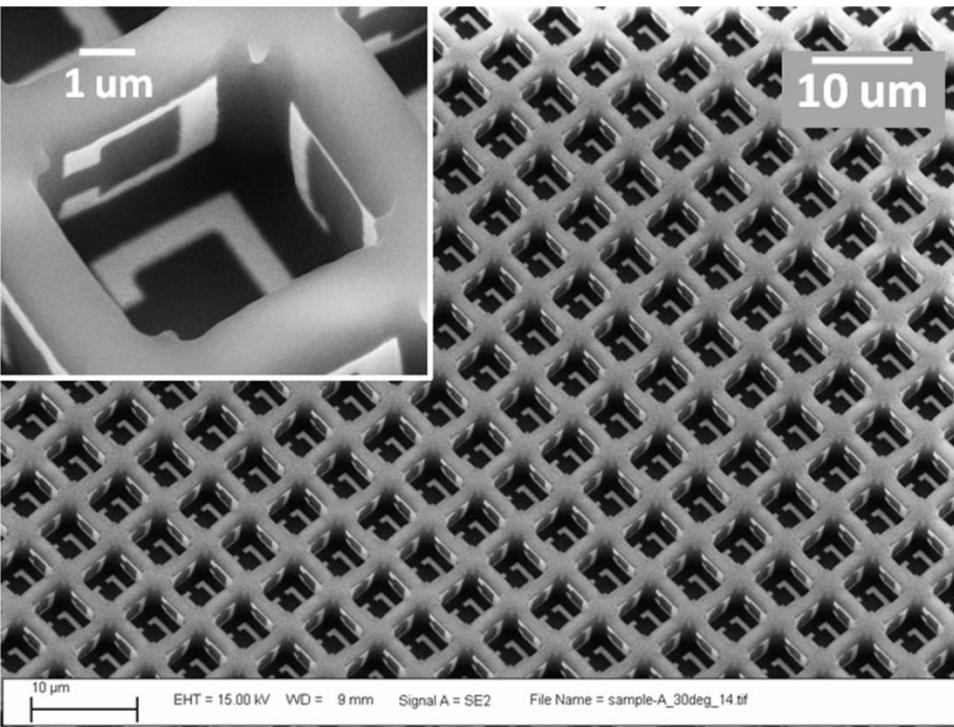
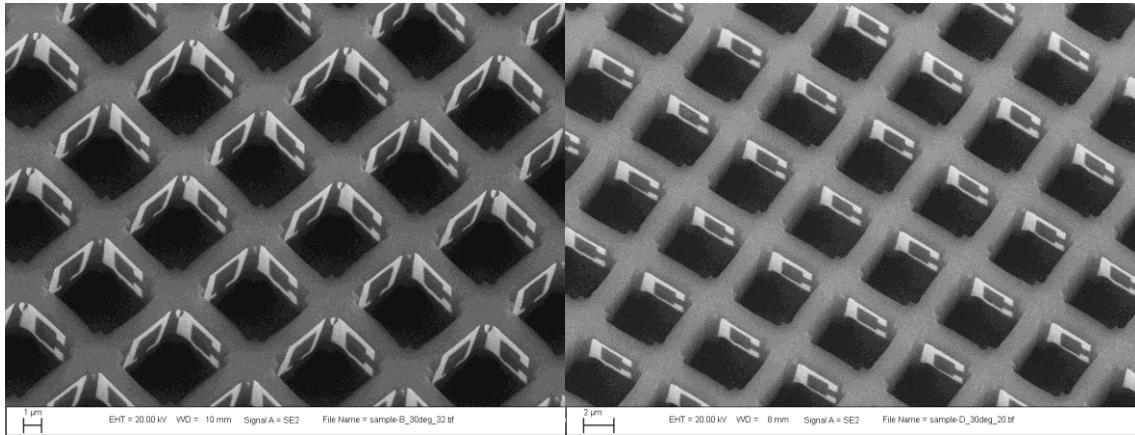
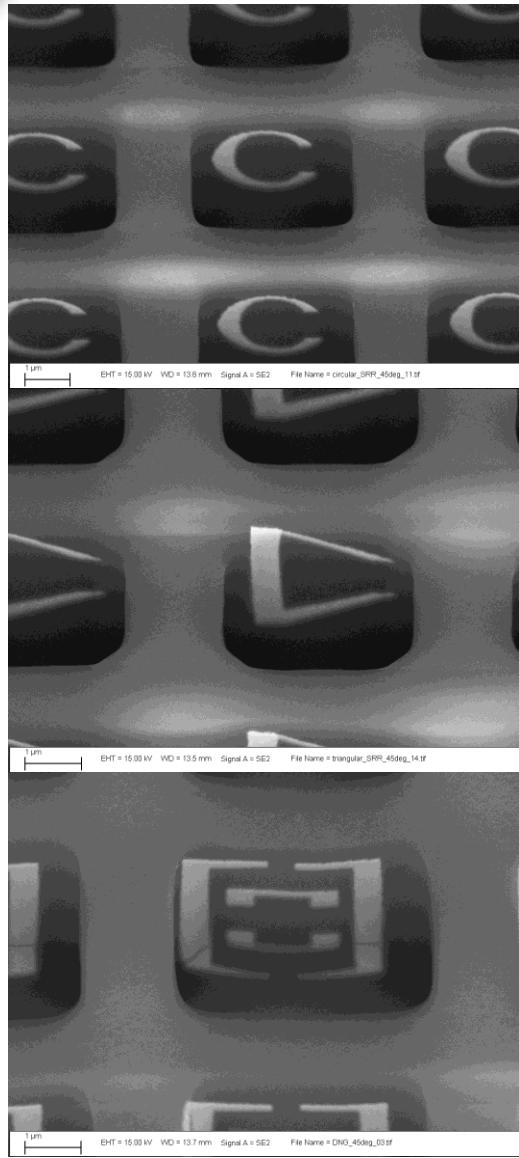


Planarize Backfill

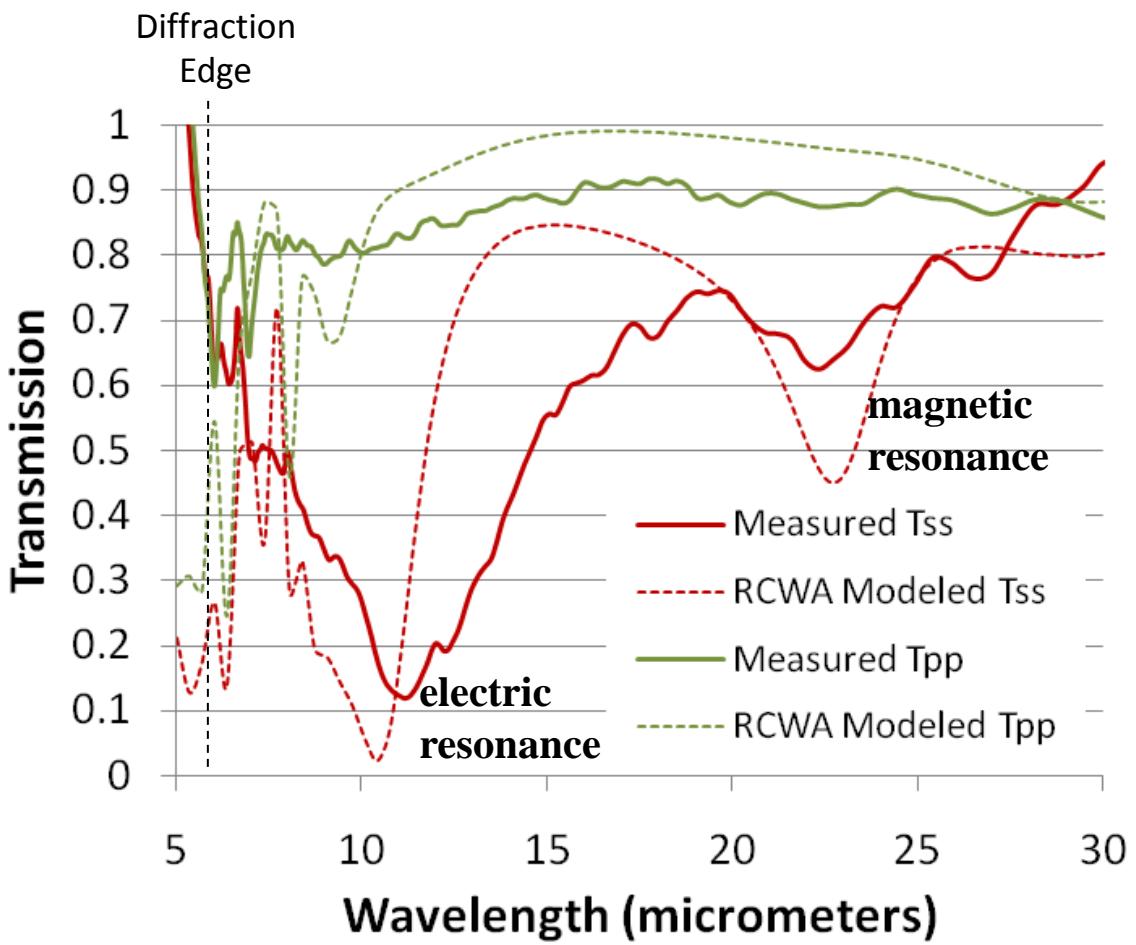
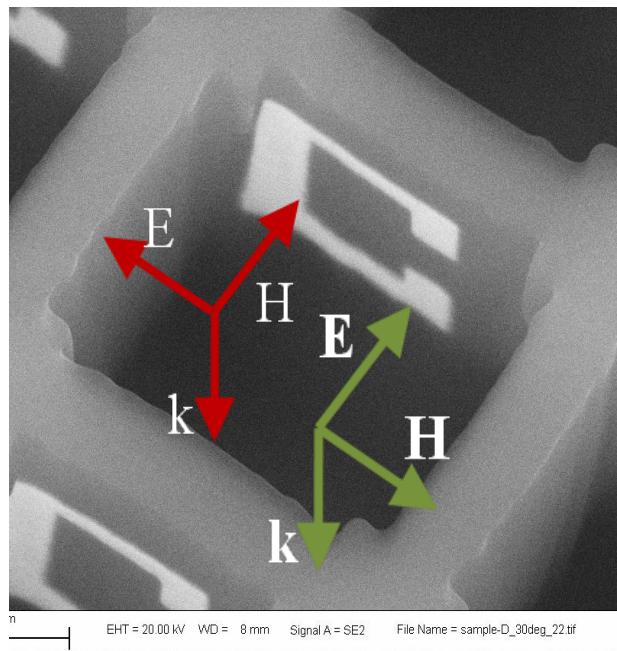
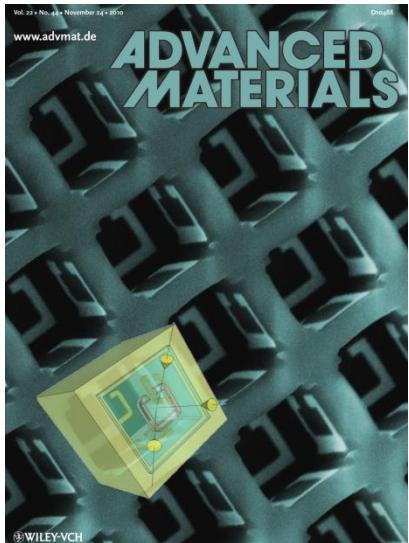


Dissolve Out Backfill

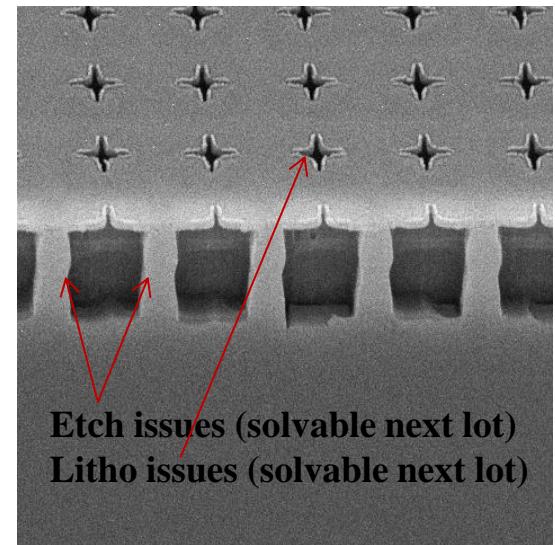
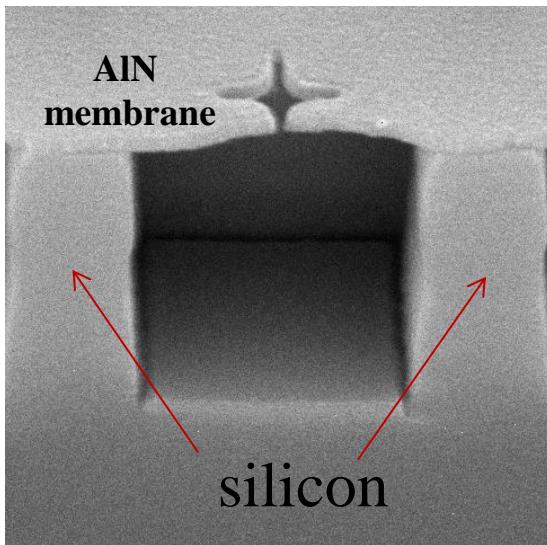
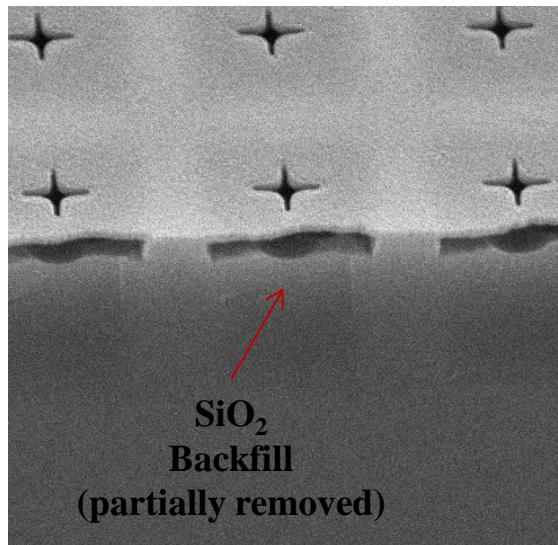
Micron-Scale Cubic Metamaterial Layers



Demonstration of Magnetic Polarization in the IR



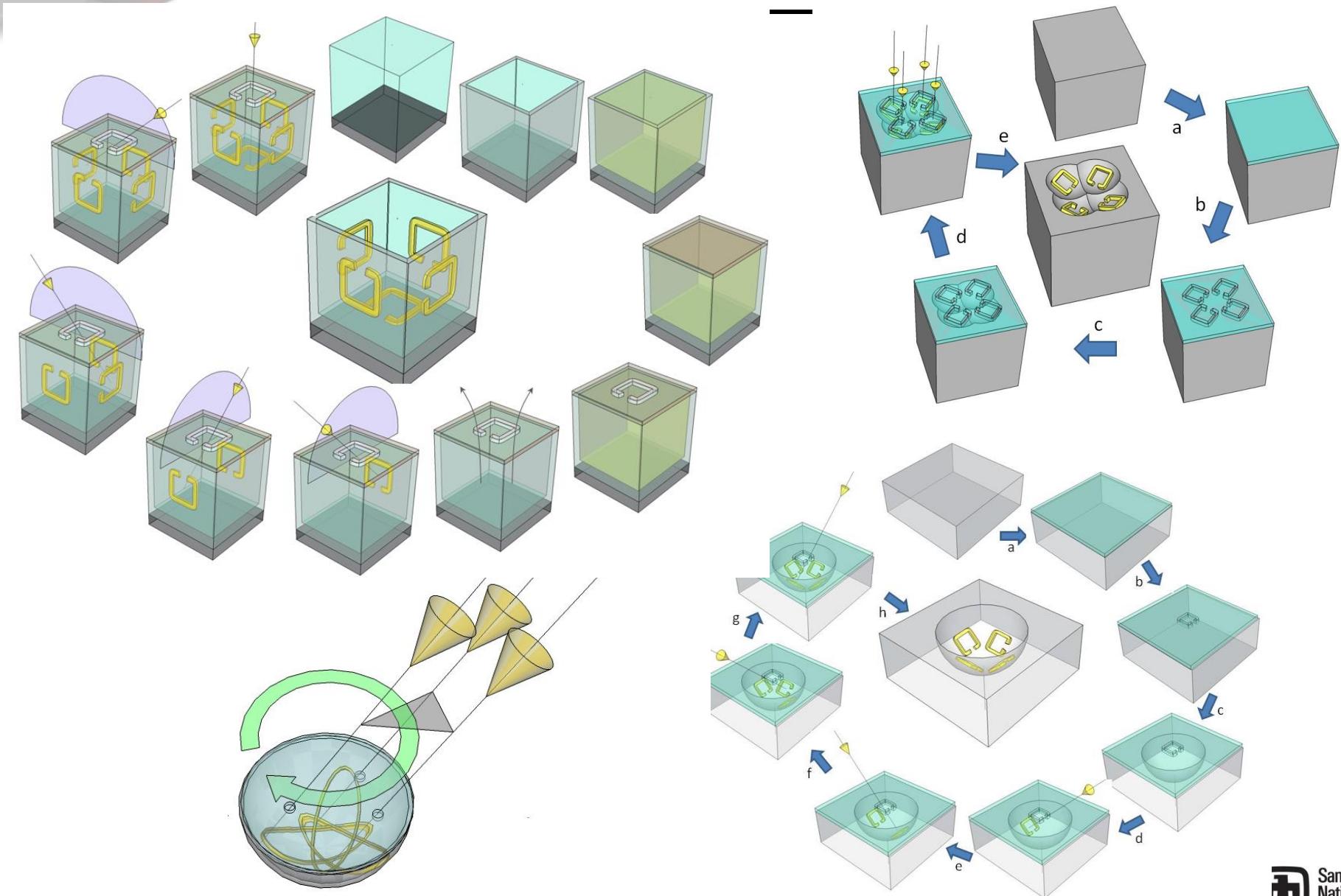
MPL : Inorganic Material Set



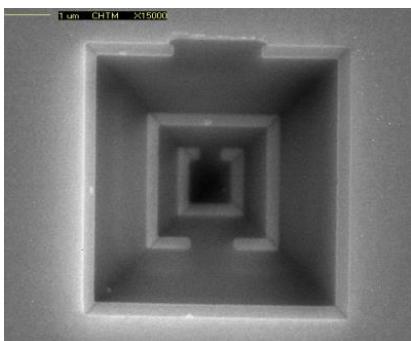
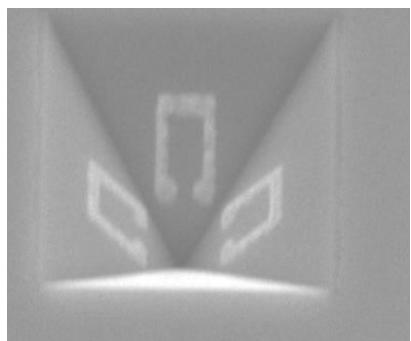
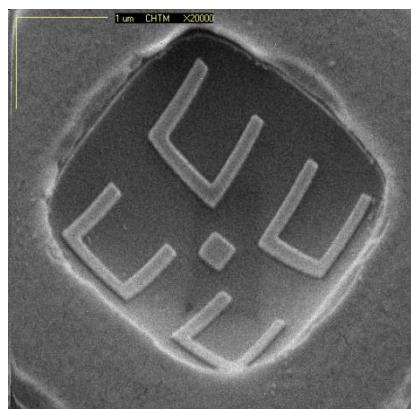
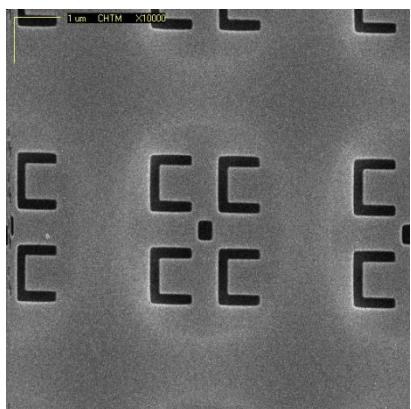
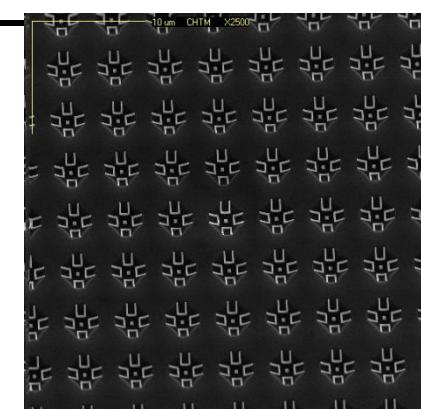
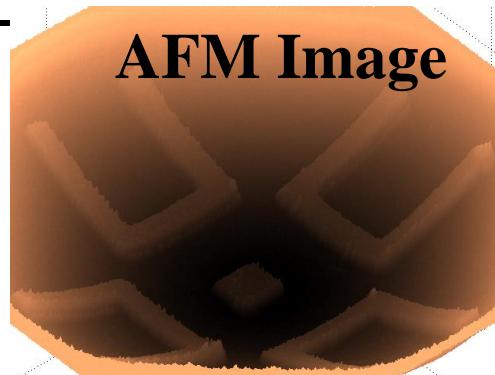
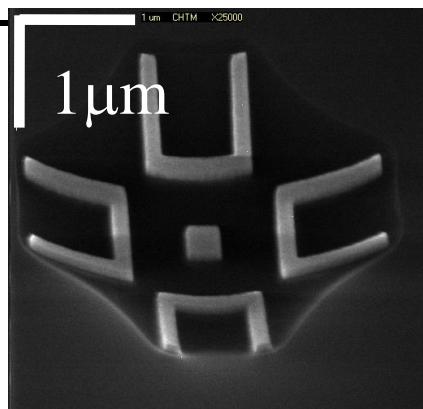
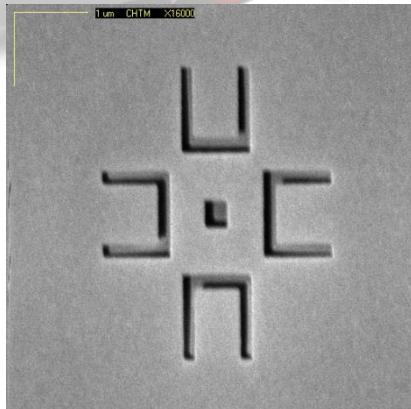
Lithography : Stepper
Inorganic backfill, CMP planarization

Subject of an upcoming LDRD : Fabrication of 3D Ics via MPL

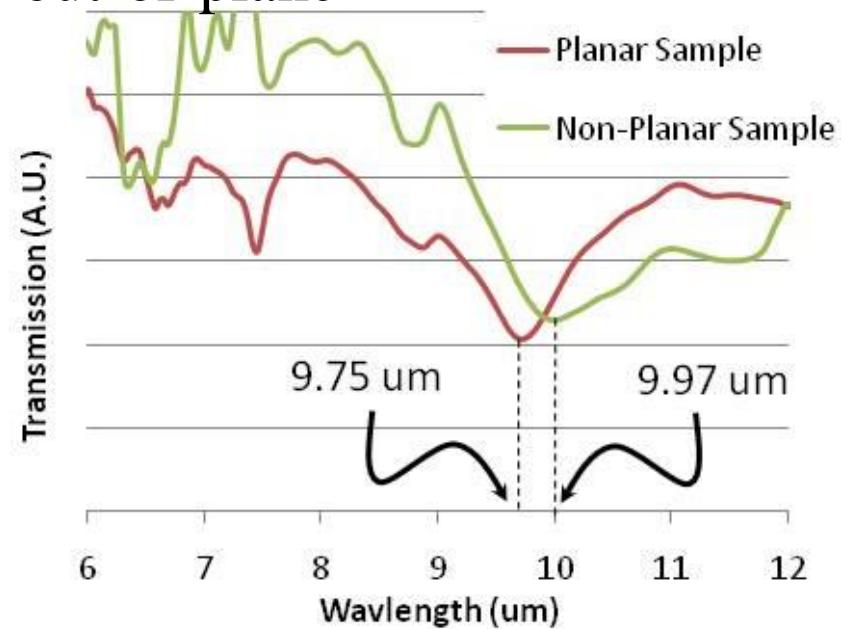
MPL At A Glance



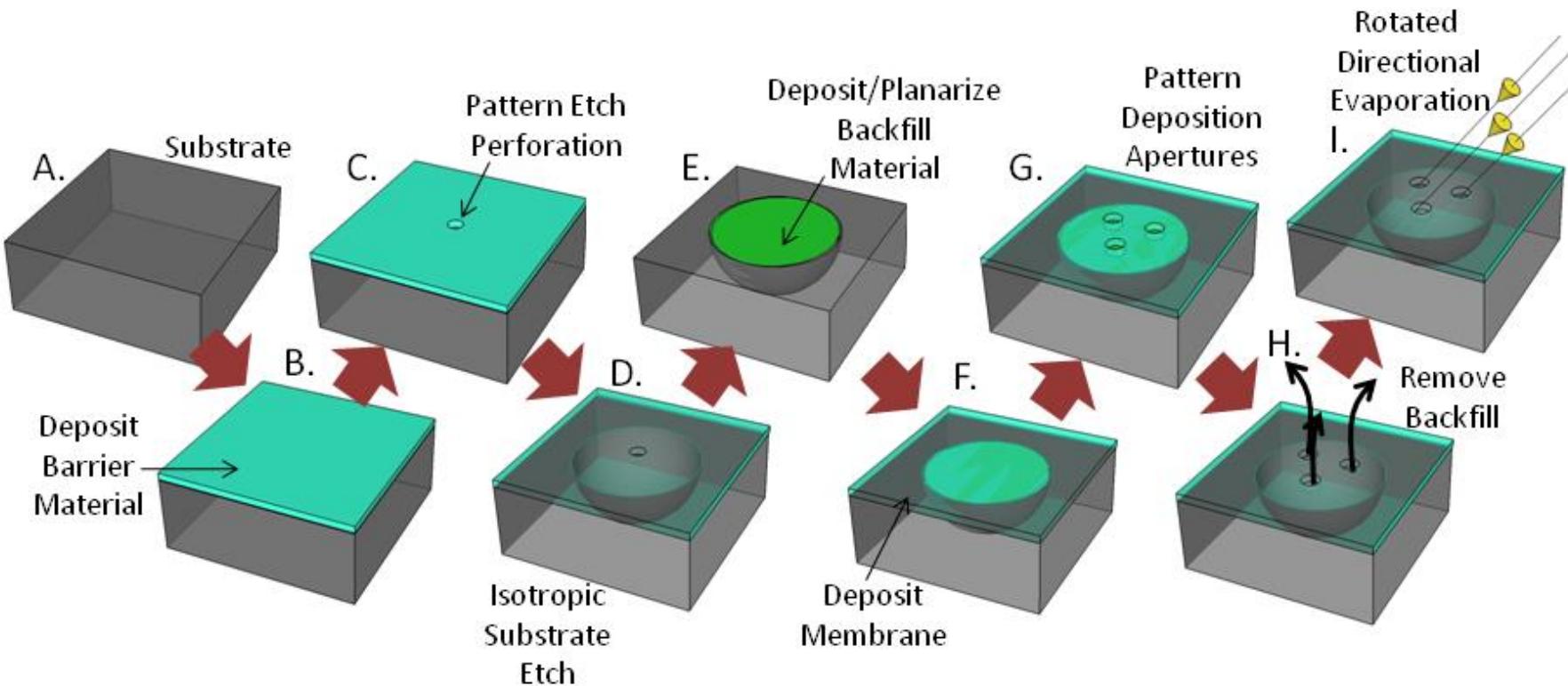
Examples of Single Evaporation SAMPL



Resonators 20°
out-of-plane

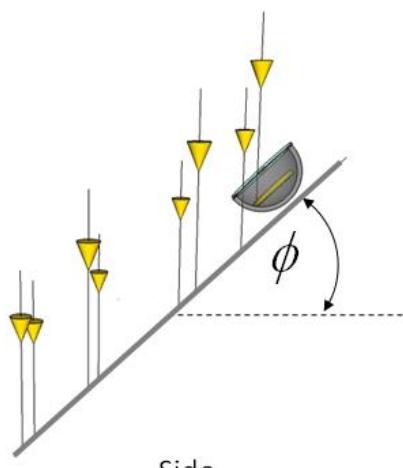
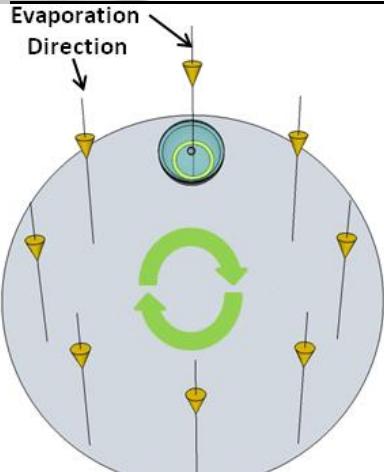


Two-Step Process Flow

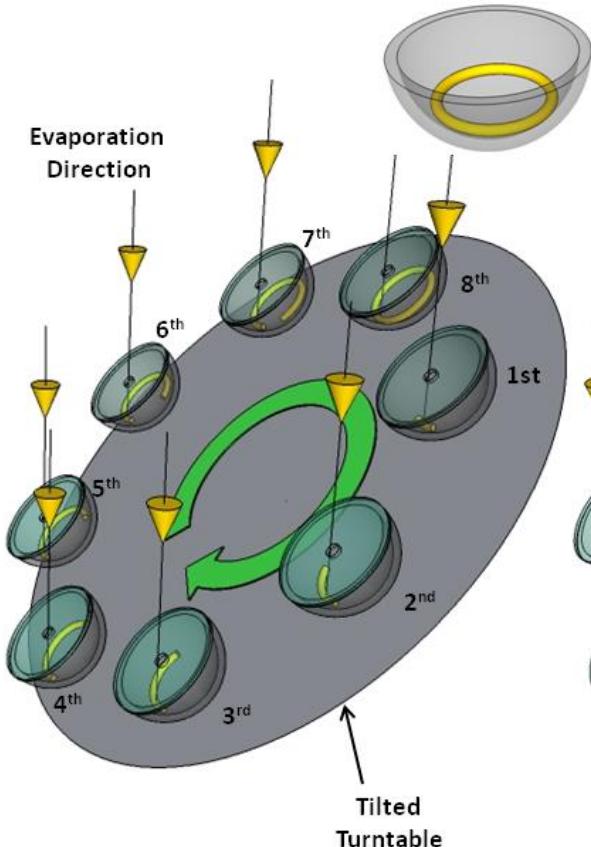


Cavity shape is now decoupled from perforation locations – wider variety of possible trace geometries.

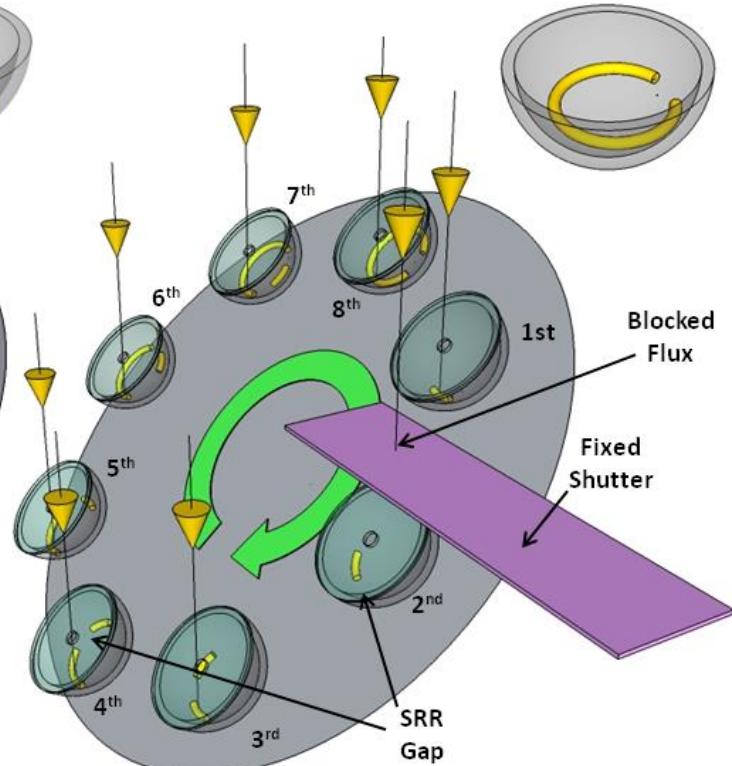
A More Practical Fabrication Approach



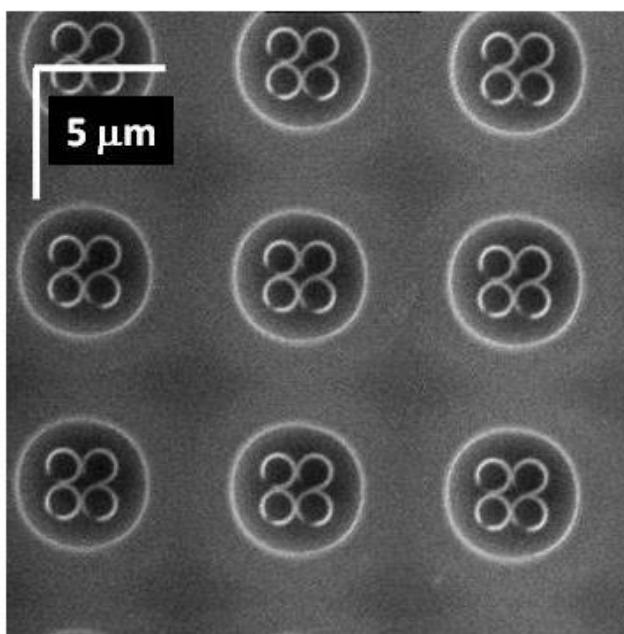
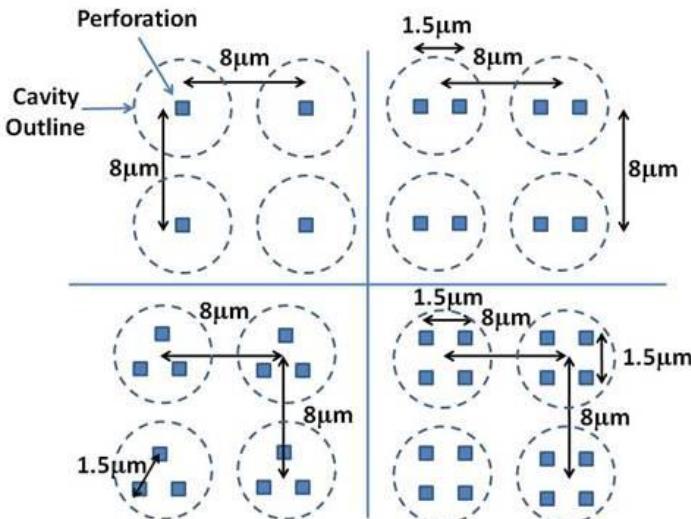
Closed Loops



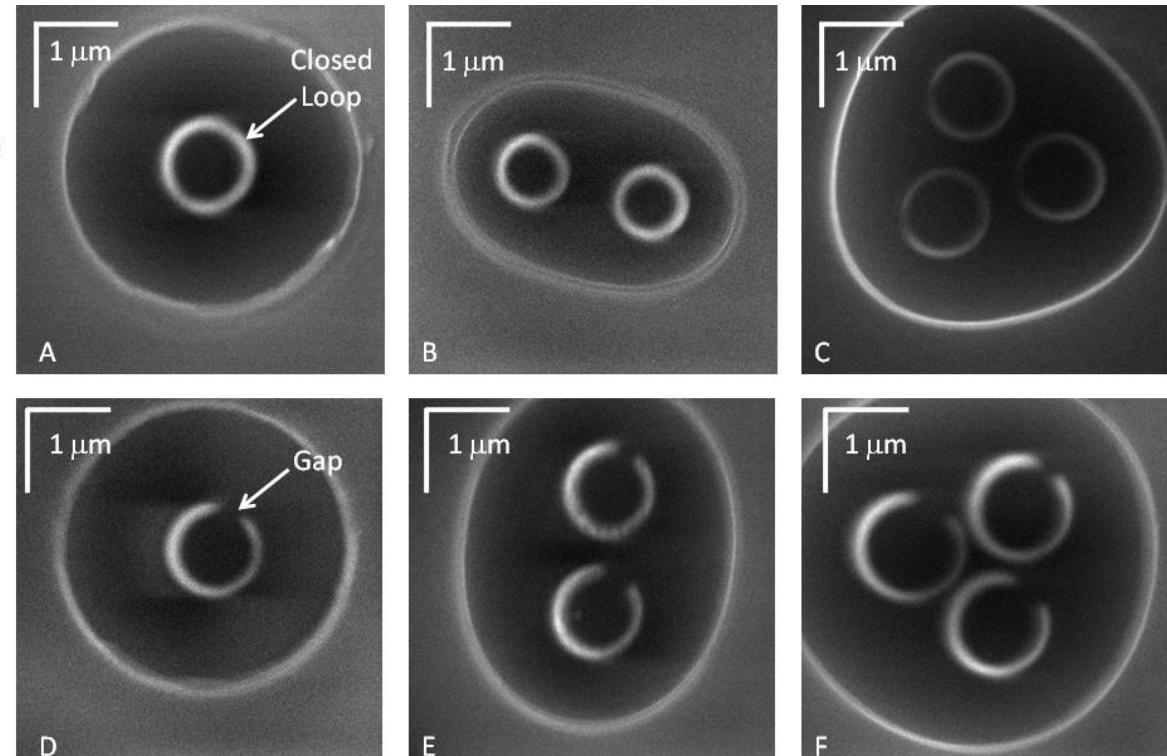
Split Loops



Preliminary Self- Aligned Fabrication Results



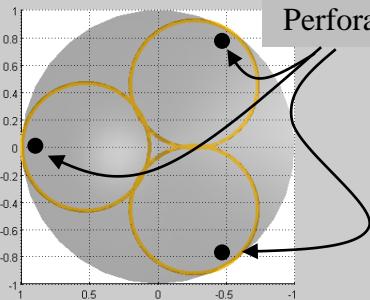
Self-aligned process flow – trace dependent cavity shape



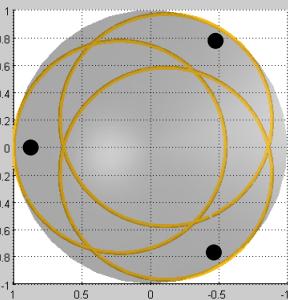
3D Multi-loop Traces

$\phi = 40^\circ$

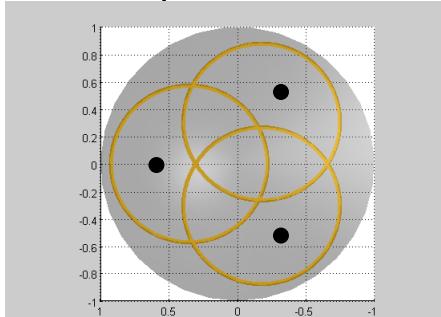
Membrane Perforation



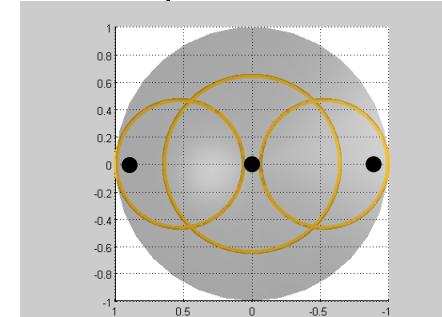
$\phi = 60^\circ$



$\phi = 40^\circ$



$\phi = 40^\circ$



A

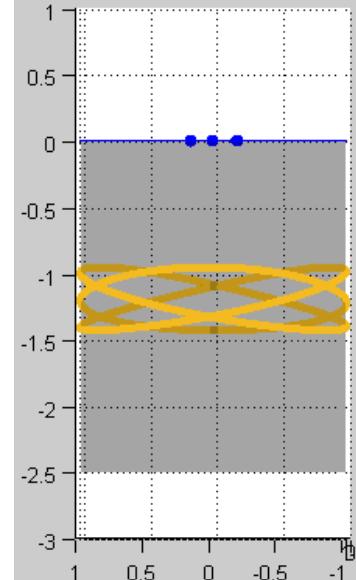
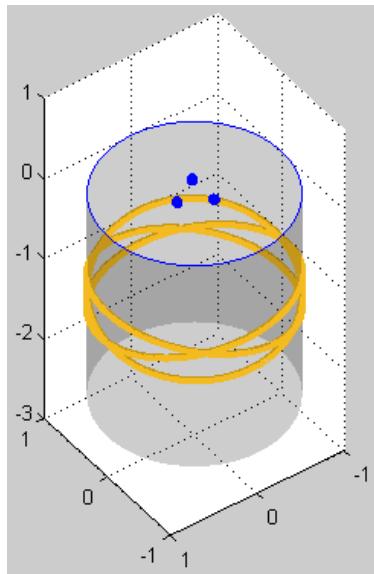
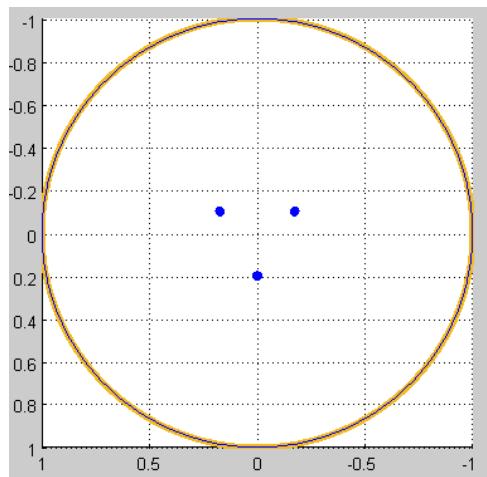
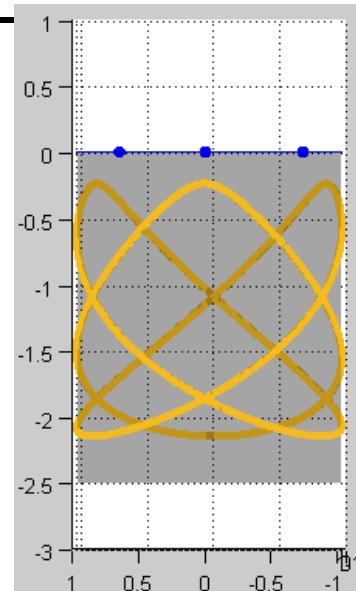
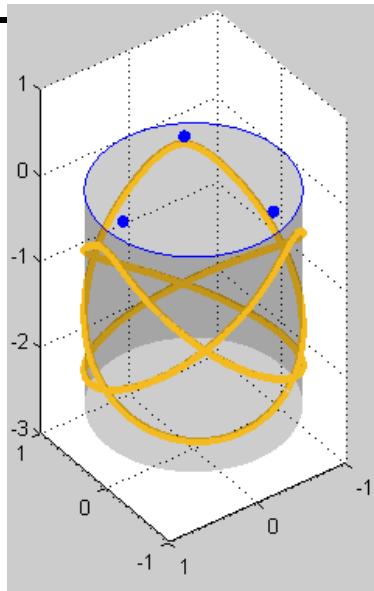
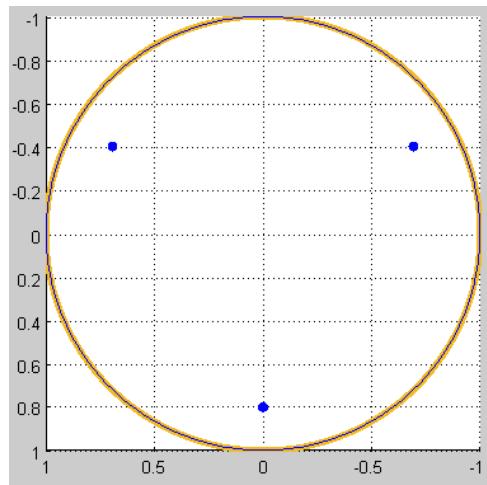
B

C

D

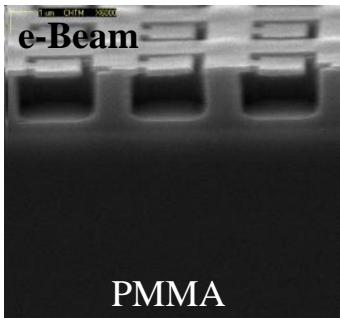
Simple geometrical variations lead to highly diverse 3D trace geometries

Dynamic MPL in a Cylindrical Cavity

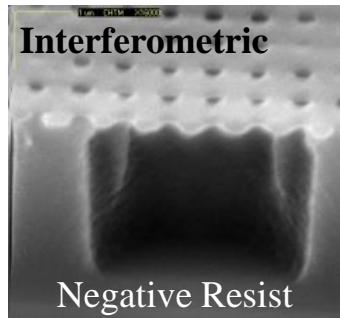


MPL Fabrication Parameter Space

Membrane Lithography

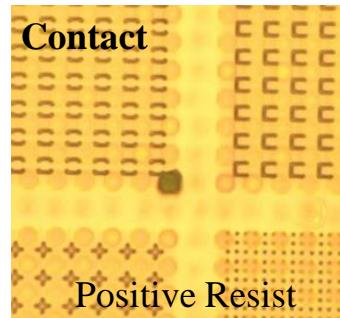


e-Beam
PMMA



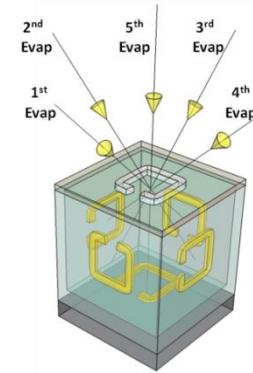
Interferometric

Negative Resist

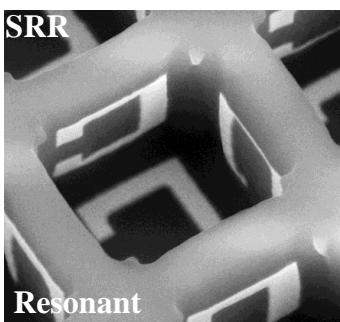


Contact

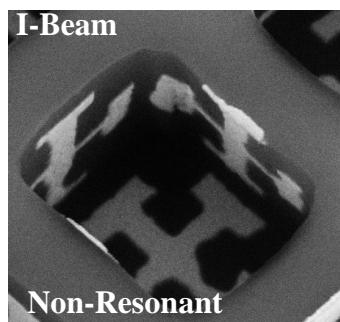
Positive Resist



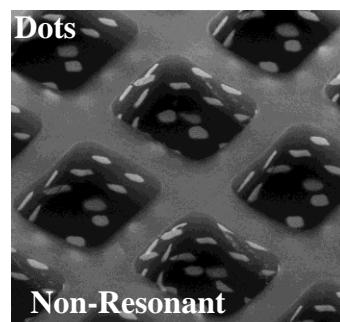
Membrane Material



SU-8
Resonant

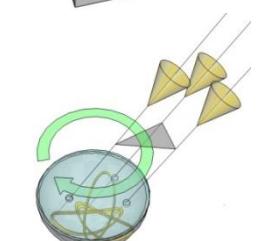
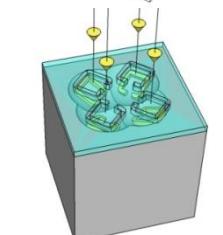
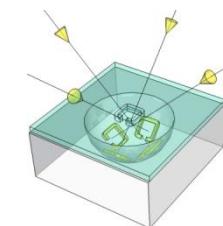


SU-8
Non-Resonant

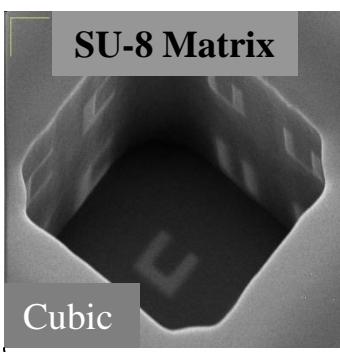


Polyimide
Dots

Polyimide
Non-Resonant

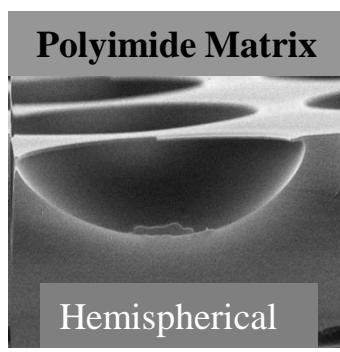


Matrix Material



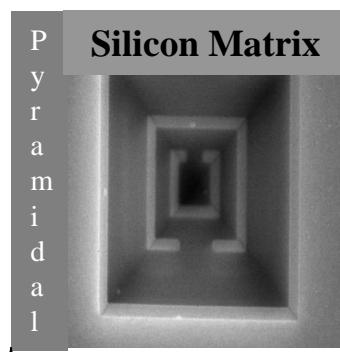
Cubic

SU-8 Matrix



Hemispherical

Polyimide Matrix



Silicon Matrix

Pyramidal

Cavity Shape

Organic

Inorganic



Conclusions

- 1.) Membrane projection lithography is a manufacturable route to micron-scale 3D metamaterials.
- 2.) Identification of a process-orthogonal material set is critical to success of MPL.
- 3.) Fabrication in 3D opens a wide parameter space of potential unit cell design possibilities.
- 4.) CMOS compatible MPL should open a wide range of new applications.

Questions?